



Sheet 1 of 2 sheet(s)

U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)		Docket No. AMAT/4714.D1/TCG/ WCVD/BG	Serial No. 09/625,336
<b>SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>		Applicant  KORI, ET AL.	Confirmation No.: 7523
(Use several sheets if necessary)		Filing Date 07/25/2000	Group 1763
Examiner MOORE, KARLA A.			

**U.S. Patent Documents**

*Examiner Initial	Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
	A1					
	A2					

**Foreign Patent Documents**

*Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation		
						YES	NO	
KU	B1	DE 196 27 017A1	01/09/1997	GERMAN W/ ENG. ABS.	H01L	21/283	<input type="checkbox"/>	<input checked="" type="checkbox"/> ABS ONLY
↓	B2	DE 198 20 147A1	07/01/1999	GERMAN W/ ENG. ABS.	H01L	21/3205	<input type="checkbox"/>	<input checked="" type="checkbox"/> ABS ONLY
	B3	FR 2 626 110	07/21/1989	FRANCE W/ ENG. ABS.	H01L	39/24	<input type="checkbox"/>	<input checked="" type="checkbox"/> ABS ONLY
	B4	FR 2 692 597	12/24/1993	FRANCE W/ ENG. ABS.	C23C	16/00	<input type="checkbox"/>	<input checked="" type="checkbox"/> ABS ONLY
	B5	JP 3-286531	12/17/1991	JAPAN	H01L	21/316	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B6	JP 3-48421	03/01/1991	JAPAN W/ ENG. ABS.	H01L	21/302	<input type="checkbox"/>	<input checked="" type="checkbox"/> ABS ONLY
	B7	JP 6-291048	10/18/1994	JAPAN W/ ENG. TRANS.	H01L	21/205	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B8	JP 8-264530	10/11/1996	JAPAN W/ ENG. TRANS.	H01L	21/3205	<input type="checkbox"/>	<input checked="" type="checkbox"/>

**OTHER ART**

*Examiner Initial	Including Author, Title, Date, Pertinent Pages, Etc.
KU	C1 "Hydrogen-Mediated Low-Temperature Epitaxy of Si in Plasma-Enhanced Chemical Vapor Deposition" by Kitagawa, et al., Applied Surface Science 159-160 (2000) pages 30-34.
	C2
	C3

Examiner KARLA MOORE	Date Considered 12/15/00
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.



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Sheet 2 of 2 sheet(s)  
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U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)		Docket No. AMAT/4714.D1/TCG/ WCVD/BG	Serial No. 09/625,399
<b>SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>		Applicant KORI, ET AL.	Confirmation No.: 7523
(Use several sheets if necessary)		Filing Date 07/25/2000	Group 1763
Examiner MOORE, KARLA A.			

#### U.S. Patent Documents

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	A1						
	A2						

#### Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
KL	B1	JP 2001-240972	09/04/2001	JAPAN W/ ENG. TRANS.	C23C	16/458	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B2	JP 2001-254181	09/18/2001	JAPAN W/ ENG. TRANS.	C23C	16/46	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B3	JP 2001-284042	10/12/2001	JAPAN W/ ENG. TRANS.	H05B	33/04	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B4	JP 2001-303251	10/31/2001	JAPAN W/ ENG. TRANS.	C23C	16/44	<input type="checkbox"/>	<input checked="" type="checkbox"/>
V	B5	JP 2001-328900	11/27/2001	JAPAN W/ ENG. TRANS.	C30B	29/68	<input type="checkbox"/>	<input checked="" type="checkbox"/>

#### OTHER ART

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
KL	C1	U.S. Patent Application Serial No. 09/605,593 Filed June 28, 2000 Entitled "Bifurcated Deposition Process for Depositing Refractory Metal Layers Employing Atomic Layer Deposition and Chemical Vapor Deposition Techniques".
KL	C2	U.S. Patent Application Serial No. 09/678,266 Filed October 3, 2000 Entitled "Method and Apparatus for Depositing Refractory Metal Layers Employing Sequential Deposition Techniques to Form a Nucleation Layer".

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(Use several sheets if necessary)		Filing Date 07/25/2000	Group 1763
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	A1					
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	A3					
	A4					
	A5					
	A6					
	A7					
	A8					
	A9					
	A10					

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**Foreign Patent Documents**

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						YES	NO
	B1					<input type="checkbox"/>	<input type="checkbox"/>
	B2					<input type="checkbox"/>	<input type="checkbox"/>
	B3					<input type="checkbox"/>	<input type="checkbox"/>

**OTHER ART**

*Examiner Initial	Document Number	Including Author, Title, Date, Pertinent Pages, Etc.
ku	C1	"Cluster Tools for Fabrications of Advanced Devices" by Dan Maydan, Extended Abstracts of the 22 <sup>nd</sup> (1990 International) Conference on Solid State Devices and Materials, Sendai, 1990, pages 849-852.
↓	C2	"Pulsed Nucleation for Ultra-High Aspects Ratio Tungsten Plugfill" Lee, et al., Proceedings of the Advanced Metallization Conference 2001, October 8-11, 2001, pages 649-654.
	C3	

Examiner **KARLA MOORE** Date Considered

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